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ATTORNEY DOCKET NO. CONFIRMATION NO. APPLICATION NO. FILING DATE FIRST NAMED INVENTOR 500.41374CX2 2471 10/658,281 09/10/2003 Seiichiro Kanno EXAMINER 20457 7590 05/05/2004 ANTONELLI, TERRY, STOUT & KRAUS, LLP FUQUA, SHAWNTINA T 1300 NORTH SEVENTEENTH STREET ART UNIT PAPER NUMBER **SUITE 1800** ARLINGTON, VA 22209-9889 3742

DATE MAILED: 05/05/2004

Please find below and/or attached an Office communication concerning this application or proceeding.

		M /
	Application No.	Applicant(s)
Office Action Summary	10/658,281	KANNO ET AL.
	Examiner	Art Unit
	Shawntina T. Fuqua	3742
The MAILING DATE of this communication appeared for Reply	ppears on the cover sheet with	the correspondence address
A SHORTENED STATUTORY PERIOD FOR REP THE MAILING DATE OF THIS COMMUNICATION - Extensions of time may be available under the provisions of 37 CFR 1 after SIX (6) MONTHS from the mailing date of this communication. - If the period for reply specified above is less than thirty (30) days, a re - If NO period for reply is specified above, the maximum statutory perio - Failure to reply within the set or extended period for reply will, by statu Any reply received by the Office later than three months after the mail earned patent term adjustment. See 37 CFR 1.704(b).	I. 1.136(a). In no event, however, may a repepty within the statutory minimum of thirty d will apply and will expire SIX (6) MONTI ate, cause the application to become ABA	oly be timely filed (30) days will be considered timely. HS from the mailing date of this communication. NDONED (35 U.S.C. § 133).
Status		
1) Responsive to communication(s) filed on <u>09</u>	<u>December 2003</u> .	
2a) This action is FINAL . 2b) ⊠ Th	is action is non-final.	
3) Since this application is in condition for allow	·	•
closed in accordance with the practice under	Ex parte Quayle, 1935 C.D.	11, 453 O.G. 213.
Disposition of Claims		
4) ☐ Claim(s) 3-8 is/are pending in the application 4a) Of the above claim(s) is/are withdr 5) ☐ Claim(s) is/are allowed. 6) ☐ Claim(s) 3-8 is/are rejected. 7) ☐ Claim(s) is/are objected to. 8) ☐ Claim(s) are subject to restriction and.	awn from consideration.	
Application Papers		
9) ☐ The specification is objected to by the Examir 10) ☑ The drawing(s) filed on 10 September 2003 is Applicant may not request that any objection to the Replacement drawing sheet(s) including the corre 11) ☐ The oath or declaration is objected to by the B	s/are: a)⊠ accepted or b)□ e drawing(s) be held in abeyance ection is required if the drawing(s	e. See 37 CFR 1.85(a).) is objected to. See 37 CFR 1.121(d).
Priority under 35 U.S.C. § 119		
 12) Acknowledgment is made of a claim for foreign a) All b) Some * c) None of: 1. Certified copies of the priority documents. 2. Certified copies of the priority documents. 3. Copies of the certified copies of the priority application from the International Bure. * See the attached detailed Office action for a list. 	nts have been received. nts have been received in Ap iority documents have been re au (PCT Rule 17.2(a)).	plication No eceived in this National Stage
Attachment(s)		
Notice of References Cited (PTO-892) Notice of Draftsperson's Patent Drawing Review (PTO-948)		mmary (PTO-413) Mail Date
3) Information Disclosure Statement(s) (PTO-1449 or PTO/SB/0) Paper No(s)/Mail Date 9/10/03.	_	ormal Patent Application (PTO-152)

Application/Control Number: 10/658,281 Page 2

Art Unit: 3742

DETAILED ACTION

Claim Rejections - 35 USC § 103

- 1. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:
 - (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 3-8 are rejected under 35 U.S.C. 103(a) as being unpatentable over Ishii (US5851298) in view of Ushikawa (US6140256) and Ratliff et al (US6492621).

Ishii discloses a plasma processing apparatus in which a wafer (W) is mounted on an upper ceramic member (38) of a stage disposed within a vacuum chamber (2), the stage including a cooling jacket (10) with a path (12) for passing coolant liquid (column 5, lines 20-22) and the upper member (6) including a heater (16) and an electrode (14) for an electrostatic chuck (14) wherein the wafer is mounted on the upper member. Ishii does not disclose a method comprising the steps of transferring the wafer to a position corresponding to the upper member of the stage, holding the wafer at the corresponding position for a predetermined period, and mounting the wafer on the upper member, step of holding includes preheating the wafer, transferring wafer to a buffer room to be cooled after processing, and transferring out of the buffer room. Ushikawa discloses a method comprising the steps of transferring the wafer to a position corresponding to the upper member of the stage, holding the wafer at the corresponding position for a predetermined period, and mounting the wafer on the upper member wherein the step of holding includes preheating the wafer (column 3, lines 64-66; column 4, lines 14-26) and Ratliff et al discloses transferring wafer to a buffer room to be cooled after processing, and

transferring out of the buffer room (column 1, lines 54-65; abstract, Figures 1A-B). It would have been obvious to one of ordinary skill in the art at the time the invention was made to have included the method of Ushikawa and Ratliff et al in the apparatus of Ishii because, preheating the wafer above the upper member of the stage allows the wafer to be heated more uniformly, and cooling the wafer in a separate buffer room allows the chamber to be maintained at the processing temperature.

Conclusion

3. Any inquiry concerning this communication or earlier communications from the examiner should be directed to Shawntina T. Fuqua whose telephone number is (703) 305-2581. The examiner can normally be reached on Monday-Friday 8-4:30 pm.

If attempts to reach the examiner by telephone are unsuccessful, the examiner's supervisor, Shawntina Fuqua can be reached on (703) 308-1327. The fax phone number for the organization where this application or proceeding is assigned is 703-872-9306.

Information regarding the status of an application may be obtained from the Patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free).

stf

April 30, 2004

Shawntina Fuqua Patent Examiner

Page 3

Art Unit 3742